



INFORMATION CITED BY APPLICANTS THAT MAY BE MATERIAL TO THE
PROSECUTION OF THE SUBJECT APPLICATION

Applicant: Y. Granik et al.

Attorney Docket No. MEGC117332

Application No.: 09/898,431

Group Art Unit: 2123

Filed: July 2, 2001

Title: METHOD OF COMPENSATING FOR ETCH EFFECTS IN
PHOTOLITHOGRAPHIC PROCESSING

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U.S. PATENT DOCUMENTS

*Examiner Initials	Cite No.	Document No.	Kind Code	Date (mm/dd/yyyy)	Name
<u>MCH</u>	U1	5,682,323		10/28/1997	Pasch et al.
<u>MCH</u>	U2	5,801,954		09/01/1998	Le et al.

FOREIGN PATENT DOCUMENTS

None

OTHER INFORMATION

None

Examiner

Date Considered

Mary C. Hogan

11/3/05

*Examiner: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. RCT:yc

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